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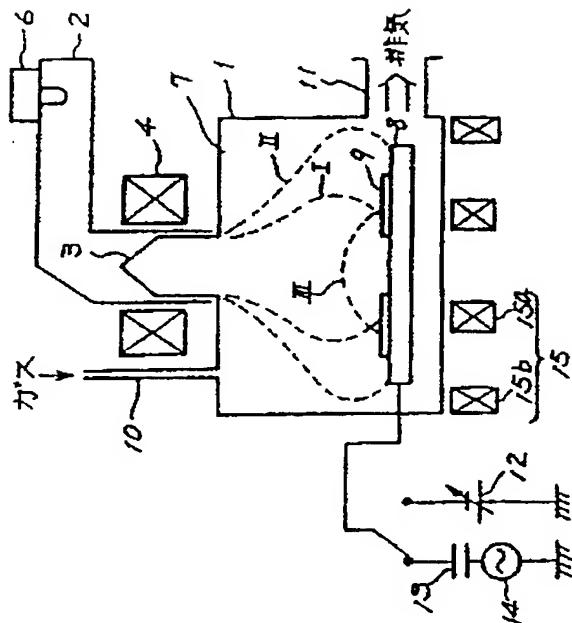
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TITLE : PLASMA TREATMENT APPARATUS



ABSTRACT : PURPOSE: To perform uniform treatment in a plasma region having a large area, by providing a plurality of magnetic field forming members, which are mutually arranged concentrically on the same plane so as to provide an interval therebetween, and a magnetic field control member to a magnetic field control means.

CONSTITUTION: The line of magnetic force generated in a vacuum chamber 1 by a magnetic field generation apparatus 4 is concentrated to the inside by an inside magnetic field forming member 15a and plasma is closed to be converged to the surface position of a specimen 9. Next, the magnetic field direction of the inside magnetic field forming member 15a is opposed to that of the magnetic field generation apparatus 4 and, at the same time, the magnetic field direction of an outside magnetic field forming member 15b is allowed to coincide with that of the magnetic field generation apparatus 4. As a result, the line III of magnetic force is generated in the vacuum chamber 1 and, at the same time, concentrated to the gap with the outer periphery of the inside magnetic field forming member 15a by the outside magnetic field forming member 15b and, therefore, a plasma distribution treatment region II can be enlarged in the vacuum chamber 1.

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